Customer No.: 31561
Application No.: 10/707,193
Docket No.: 11932-US-PA

#### **AMENDMENTS**

### In The Claims

1. (currently amended) An InAs/GaAs quantum dot light emitting diode which is formed by turning off an As shutter and using As background concentration for epitaxy, comprising:

a Si-doped GaAs substrate, a N-type structure, an undoped quantum well, a series of quantum dot layers, spacer layers, a barrier layer and a P-type structure, wherein the Si doped GaAs substrate is a (001)±1° substrate and has dopant concentration from about 1×10<sup>18</sup> to about 1×10<sup>19</sup> cm<sup>-3</sup> when substrate temperature is raised to 610°C to about 650°C.

2. (original) The InAs/GaAs quantum dot light emitting diode of claim 1, wherein an InAs quantum dot layer is formed by using the As background concentration for epitaxy when the As shield is turned off.

#### 3. (canceled)

4. (currently amended) The InAs/GaAs quantum dot light emitting diode of claim [[3]]1, wherein the N-type structure comprising a GaAs buffer layer having a thickness about from 500 nm to about 2000 nm and dopant concentration from about 1×10<sup>18</sup> to about

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5×10<sup>18</sup> cm<sup>-3</sup> formed on the substrate, and a Al<sub>x</sub>Ga<sub>1-x</sub>As cap layer having a thickness about

from 200 nm to about 800 nm and dopant concentration from about 1×1018 to about 5×1018

cm<sup>-3</sup> formed on the GaAs buffer layer, wherein x is about 0.3-0.7 when substrate

temperature is raised to 610°C to about 650°C.

5. (currently amended) The InAs/GaAs quantum dot light emitting diode of claim

[[3]]1, wherein the undoped quantum well layer comprises two to ten multi-layer GaAs

/undoped Al Gai. As quantum wells formed on the cap layer, wherein each quantum well

has a thickness about from 3 nm to about 7 nm, and x is about 0.3-0.7 when substrate

temperature is down to 580°C to about 615°C.

6. (original) The InAs/GaAs quantum dot light emission diode of claim 5, wherein

the quantum dot layer, the spacer layer and the barrier layer comprise three to ten InAs

quantum dot molecular layers formed on the quantum wells, wherein each quantum dot

molecular layer has a thickness from about 2.5 molecular layer (ML) to about 4.5 ML,

when substrate temperature is down to 470°C to about 520°C; the each quantum dot layer

covered with an undoped InAs spacer layer having a thickness from about 10 nm to about

40 nm; and a GaAs barrier layer having a thickness from about 10 nm to about 50 nm is

formed on the last spacer layer.

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7. (original) The InAs/GaAs quantum dot light emission diode of claim 6, wherein the P-type structure comprises a Al Ga, As cap layer 8 having a thickness from about 300 nm to about 700 nm formed on the GaAs barrier layer, wherein x is about 0.3-0.7 and Be concentration is from about 1×1018 to about 1×1019 cm; 3; and a GaAs contact layer having a thickness from about 300 nm to about 1000 nm formed on the cap layer, which is doped with Be having concentration from about 5×1018 to about 5×1019 cm3.

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